

US Department of Commerce Patent and Trademark Office Form PTO-1449 (Modified)		Atty. Docket No.: 42390P11370		Application No.: Not Yet Assigned		
		Applicant: Ohfuji et al.		09-965280 09/26/01 10-965280		
		Filing Date: Concurrently Herewith				
US Patent Documents						
Examiner's Initials	Date	Document Number	Name	Class	Sub- Class	Filing Date
SPM	01/02/01	6,169,274 B1	Kulp	—	—	03/01/99
SPM	03/07/00	6,034,771	Rangarajan et al.	—	—	11/04/98
SPM	08/08/00	6,100,012	Shi	—	—	07/06/98
SPM	08/08/00	6,100,506	Colelli, Jr. et al.	—	—	07/26/99
SPM	05/22/01	6,235,439 B1	Whiting	—	—	05/19/99
Foreign Patent Documents						
Examiner's Initials	Date	Document Number	Country	Class	Sub- Class	Translation
Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)						
SPM		Section 2.7 Resists, SPIE Handbook of Microlithography, Micromachining and Microfabrication, Volume 1: Microlithography. [online] [retrieved on 8-3-01] Retrieved from the Internet <URL: http://www.cnf.cornell.edu/SPIEBook/spie7.htm Pgs. 1-11				
SPM		Negative e-beam resist SAL603-0.45 [online] [retrieved on 8-3-01] Retrieved from the Internet: <URL: http://www.nanophys.kth.se/nanophys/facilities/nfl/resists/sal603.html Pages 1-3.				
SPM		Alexei L. Bogdanov, "Use of SU-8 Negative Photoresist for Optical Mask Manufacturing MAX-Lab, University of Lund, SE-221 00, Lund Sweden. [online] Pages 1-11 http://www.maxlab.luy.se/beamlines/bld811/2000/Su8.pdf				
SPM		R.D. Allen, G.M. Wallraff, D.C. Hofer and R.R. Kunz; "Photoresists for 193-nm Lithography", IBM Journal of Research and Development, Vol. 41, No. 1/2 -Optical lithography.[online] [retrieved on 6-27-01] Retrieved from the Internet: <URL: www.research.ibm.com/journal/rd/411/allen.html Pages 1-10				
SPM		SPIE Volume 2512; Masumi Arai, Hiroyuki Inomata, Toshihisa Nishimura, Masa-aki Kurihara and Naoya Hayashi; "Application of Chemically Amplified Resists to Photomask Fabrication". Micro Products Research Laboratory, Micro Products Division, Dai Nippon Printing CO., Ltd., Japan. Pages 74-87				
Examiner Mohamedulla		Date Considered 8/10/04				

Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw a line through the citation if not in conformance and not considered. Include a copy of this form with the next communication to the applicant

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Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)							
		SPIE Volume 1086, Advances In Resists Technology and Processing.(1989) Deep UV ANR Photoresists For 248 nm Excimer Laser Photolithography. James W. Thackeray, George W. Orsula, Edward K. Pavelchek, Dianne Canistro; Shipley Co., Inc., Newton Massachusetts. Leonard E. Bogan Jr., Amanda K. Berry, Karen A. Graziano; Rohm and Hass Co., Inc. Philadelphia Pennsylvania. Pages 34-47.					
87h		SPIE Volume 2793, A Chemically Amplified Resist Process For 0.25 μ M Generation Photomasks, Miki Katsumata, Hirochi Kawamura, Minoru Sugara and Satoru Nozawa, MOS LSI Division, Semiconductor Company, Sony Corporation, Japan. Pages 96-104					
Examiner	Mohamed Ull			Date Considered			8/10/04

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